Data & Configuration

Description: Diffusion (Amorphous Anneal, α-Si）

Manufacturer: TEL

Model: FORMULA

Wafer Size: 300mm

Vintage: 2009

S/W Version: 2.0

Configuration:

< Basic Configuration >

Thorough-put: 50 wafers in Batch

Temperature: 850℃

Gas Unit: PH3 1% ,F2, H2, O2 ,

System Controller: WAVES/Model780

Heater: Mid-Temp VCM-50-XXX

Exhaust Controller: CKD VEC

EXH Box: Standard Type (190 cm width)

Dry Pump: Exclude

< Gas Configuration >

Gas Pressure Flow Connection Type

Gas Box

P-N2 0.5MPa 92 L/min φ1/4”UJR

1%PH3/He 0.2MPa 5 L/min φ1/4”UJR

H2 0.2MPa 5 L/min φ1/4”UJR

O2 0.2MPa 5 L/min φ1/4”UJR

F2 0.2MPa 5 L/min φ1/4”UJR

EXH Box

P-N2	-	-	φ3/4”SWG
P-N2	-	-	φ1/2”SWG
P-N2	-	-	φ1/2”SWG
D-N2	-	-	φ3/8”SWG

D-N2 - - φ3/8”SWG

D-N2 - - φ1/4”SWG

Vacuum 20KPa - φ3/8”SWG

RCU

P-N2 0.7MPa 1200 L/Min

φ3/4”SWG D-N2 0.7MPa -

φ1/4”SWG

P-N2 - - φ3/4”SWG

P-N2 - - φ1/2”SWG

P-N2 - - φ1/2”SWG

D-N2 - - φ3/8”SWG

D-N2 - - φ3/8”SWG

D-N2 - - φ1/4”SWG

Pump

D-N2 0.7MPa - φ1/4”SWG

D-N2 0.7MPa 110 L/min

φ1/2”SWG